

ABSTRACT OF THE DISCLOSURE
EXPOSURE APPARATUS AND ARTICLE MANUFACTURING METHOD

An exposure apparatus that performs a job process of exposing each of a plurality of substrates while exchanging the substrate is provided. The apparatus comprises a substrate holder configured to hold a substrate, and a controller configured to control the job process. The controller corrects, based on a relationship between an elapsed time of the job process and a substrate deformation amount, an overlay error generated due to deformation of the substrate, and exposes the substrate. In the relationship, the substrate conveyed to the substrate holder upon a substrate exchange is given an initial deformation amount corresponding to residual heat of the substrate holder at the time of the substrate exchange.

(Figure 1)